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## INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(use as many sheets as necessary)

of

Complete II Known				
Application Number	10/809,317			
Filing Date	03/24/2004			
First Named Inventor	G. Ramanath			
Group Art Unit	2813			
Examiner Name	-Kielen, Erik J Colleen Rodo			

Attomey Docket Number 5002.02-1

	U.S. PATENT DOCUMENTS						
Examiner	Cite	Document Number	Publication Date/ Issue Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear		
Initials *	No.1	Number - Kind Code <sup>2</sup> (if known)					
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RR	AJ.	US - 5,939,150	08-1999	Stelzle et al.			
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Examiner	Cite	Foreign Patent Document		Name of Patentee or	Pages, Columns, Lines, Where Relevant		
Initials*	No.1	Country Code <sup>3</sup> - Number <sup>4</sup> - Kind Code <sup>5</sup> (if known)	Publication Date MM-DD-YYYY	Applicant of Cited Document	Passages or Relevant Figures Appear	T <sup>6</sup>	
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OTHER PRIOR ART NON PATENT LITERATURE DOCUMENTS					
Examiner Initials *	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T²		
(R)	AL	Ahrens, C. et al., "Electrical characterization of conductive and non-conductive barrier layers for Cu-metallization," Applied Surface Science, 1995, pp. 285-290, Vol. 91.			
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Examiner Signature	College Qof	Date Considered	12/1/05

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STA	TEMENT B	Y A	PPLICANT	First Named Inventor	G. Ramanath	
				Group Art Unit	2813	1
	(use as many she	ets as	necessary)	Examiner Name	Kielen, Erik J Colleen Pa	gers
Sheet	2	of	2	Attorney Docket Number	5002.02-1	7

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(OP)	AR	Sekiguchi, A. et al., "Microstructural and morphological changes during thermal cycling of Cu thin films," J. Japan Inst. Metals, April 2000, pp. 379-382, Vol. 64(5).
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(P)	AT	Porterfield, Inorganic Chemistry, A Unified Approach, Addison-Wesley: Reading, Massachusetts, 1984, pp. 487-488.
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<sup>3</sup> Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup> For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup> Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. Applicant is to place a check mark here if English language Translation is attached.